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5077-000073/COA	
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Toshiya Yokogawa, et al.	
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Ref. Desig.	Examiner's Initials	Document Number	Date	Name	Class/ Subclass	(If appropriate) Filing Date
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2.		4,882,609	11/21/1989	Schubert, et al.		
3.		6,388,272	5/14/2002	Odekirk		
. 4.		5,488,237	1/30/1996	Kuwata [New art]		

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2.		WO 01/93339 A1	12/6/2001	WIPO		Abstract
3.		EP 0612104 A2	8/24/1994	Europe		
4.		JP 54-132173	10/13/1979	Japan		Abstract
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1.		D.W. Van der Weide, "Delta-doped Schottky diode nonlinear transmission lines for 480-fs, 3.5-V transients", Applied Physics Letters, Vol. 65, No. 7, 15 August 1994, pp. 881-883.	

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3.		Shui Jinn Wang, et al., "Schottky/Two-Dimensional Hole Gas Silicon Barrier Diodes with Single and Coupled Delta-Doped Wells", Jpn. J. Appl. Phys. Vol. 33, No. 4B, Part 1, 1 April 1994, pp. 2429-2434.
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9.		"Vertical Hot-Wall Type CVD for SiC Growth", Kunimasa Takahashi, et al., Materials Science Forum Vols. 338-342 (2000), pp. 141-144.
10.		"Electronic Properties of Nitrogen Delta-Doped Silicon Carbide Layers", Toshiya Yokogawa, et al., Mat. Res. Soc. Symp. Proc. Vol. 640 (2001), pp. H2.5.1-H2-5-6.
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1.		Preliminary Manuscript of the 45 th Lecture Presentation by Japan Society of the Applied Physics, Volume No. 1, page 422, 30p-YG-4, March 28, 1998.		
2.		Notice of Reasons of Rejection for Japanese Patent App. No. 2001-566193 mailed September 16, 2003, and English translation.		

^{*} Japanese Patent App. No. 06310536 A corresponds to U.S. Patent No. 5,493,136.

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